

AMENDMENTS TO THE SPECIFICATION

Please amend the paragraph that begins at page 3, line 17 of the specification to read as follows:

Following the formation of the inter-digitated capacitor structure, a layer of aluminum or other conductive interconnect material is deposited over the capacitor structure and etched to provide a first conductive [contact] electrode 103 to the N-type dopant region 104 [(see Fig. 1)] and a second conductive [contact] electrode 105 to the P-type dopant region 106 [(see Fig. 1)]. The first conductive electrode 103 and the second conductive electrode 105 are shown in dashed lines in Fig. 1.